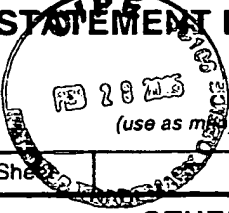



¹ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. * Applicant is to place a check mark here if English language Translation is attached.

Substitute for Form 1449B/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT  (use as many sheets as necessary)		Complete if Known	
		Application Number	10/635,344
		Filing Date	August 6, 2003
		First Named Inventor	Alan E. Delahoy et al.
		Group Art Unit	1753
		Examiner Name	Unknown Ver Steeg
Sheet 1 of 2	Attorney Docket Number	ENPI 0101 PUS	
OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
SHV		"Deposition Schemes for Low Cost Transparent Conductors for Photovoltaics", A.E. Delahoy & M. Cherny, Mat. Res. Symp. Proc., Vol. 426, 1996, pgs. 467-477	
SHV		"High-Rate Low Kinetic Energy Gas-Flow-Sputtering System", K. Ishii, J. Vac. Sci. Technol. A, Vol. 7, No. 2, 1989, pgs. 256-258	
SHV		"Hollow Cathode Discharge Sputtering Device for Uniform Large Area Thin Film Deposition", H. Koch, J. Vac. Sci. Technol. A., Vol. 9, No. 4, 1991, pgs. 2374-2377	
SHV		"Zirconia Thin Film Deposition on Silicon by Reactive Gas Flow Sputtering: The Influence of Low Energy Particle Bombardment", T. Jung & A. Westphal, Mater. Sci. Eng., A140, 1991, pgs. 528-533	
SHV		"High Rate Deposition of Alumina Films by Reactive Gas Flow Sputtering", T. Jung & A. Westphal, Surf. Coat. Technol., 59, 1993, pgs. 171-176	
SHV		"Gas Flow Sputtering of Oxide Coatings: Practical Aspects of the Process", Th. Jung, T. Kälber, V.v.d. Heide, Surf. Coat. Technol., 86-87, 1996, pgs. 218-224	
SHV		"New DC Sputter Sources for the Large Scale Deposition of Oxide Films", M. Höfer, A. Jung, T. Jung, H.-U. Kricheldorf & F. Schmidt, Proc. 43 rd SVC Annual Tech. Conf., 2000, pgs. 287-292	

Examiner Signature		Date Considered	April 14, 2005
--------------------	---	-----------------	----------------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹Unique citation designation number. ²Applicant is to place a check mark here if English language Translation is attached.